

PLENARY SESSIONS

N87-16400

PROCESS RESEARCH AND DEVELOPMENT

JET PROPULSION LABORATORY

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Processing Overview

- 1975 to 1985 progress in low cost processing has reached a plateau
- Current emphasis upon high efficiency
- New cell designs; will need process development

Major Processing Categories

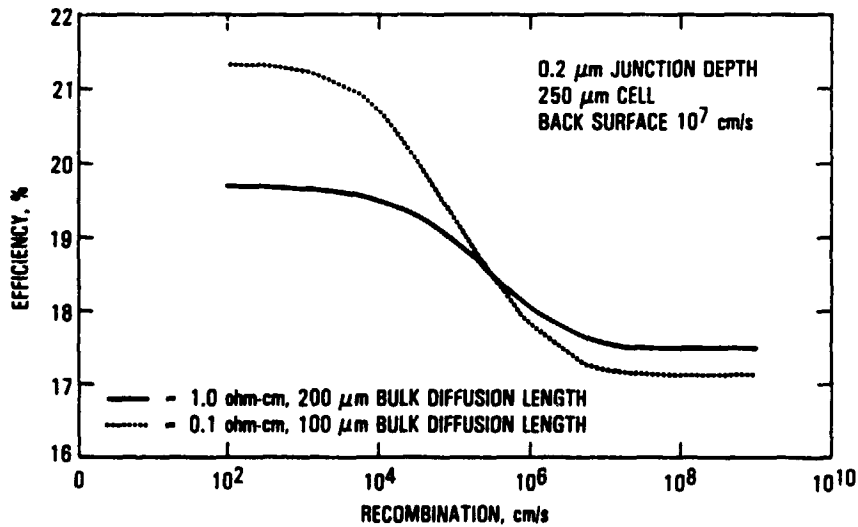
- **Surface preparation:** Damage removal etch
Passivation
A-R coat
BSR
- **Junction formation:** Diffusion
BSF
Edge isolation
- **Metallization:** Front and back
- **Assembly:** Cell interconnection
Encapsulation
Framing
Cable wiring
- **Sequences:** Relationships when combining individual processes

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Surface Preparation

1975	1985	Future
Acid etch	Hydroxide etch	Hydroxide, then acid Etch
Polymer anti-reflection (A/R)	Texture with polymer or dielectric A/R	A/R matched to passivation
\$1.22/W	\$0.20/W	\$0.10 to \$1.00/W

Efficiency Versus Front Surface Recombination Velocity*

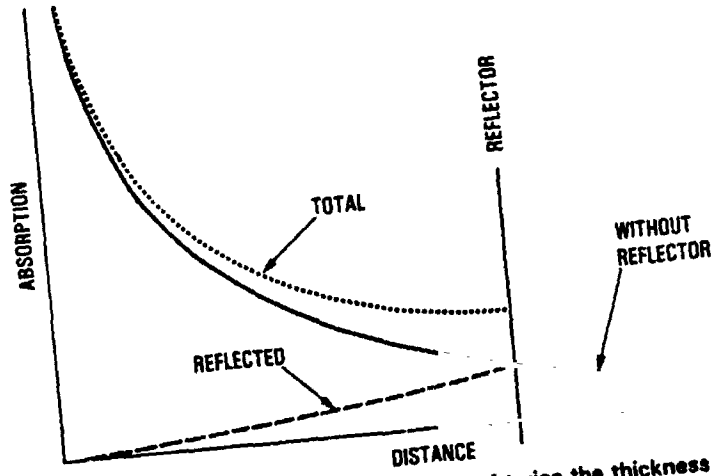


When the front surface recombination velocity is brought below 10^5 cm/s, lower resistivity (0.1 Ω -cm) material outperforms 1.0 Ω -cm material even when the bulk diffusion length is less

*From E.I.H. Lin

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Back Surface Reflector (BSR)



The use of a BSR is better than a cell of twice the thickness because the reflected photons are absorbed nearer to the junction. This means that bulk material with lesser bulk diffusion length can be utilized efficiently.

Junction Formation

1975	1985	Future
0.4 μm junction	0.3 μm	0.2 μm
Ohmic back	BSF	BSR*
\$0.43/W	\$0.28/W	\$0.15 to \$1.00/W

*Not a junction process; requires surface passivation.



Metallization


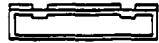
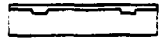

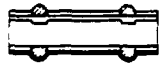
1975	1985	Future
Mask and Ni plate Solder dip	Screen print Ag	Laser writing plate up
Full back	Aluminum back with solderable pads	Gridded back
\$1.00/W	\$0.30/W	\$0.10 to \$0.20/W

Assembly

1975	1985	Future
CZ PF = .6 Interconnectors	CZ PF = .8 Redundant ribbons	Ribbon PF = .9 Redundant ribbons
Soldered Potted in polymer Metal back mount	Soldered Bonded to glass Frame mounted	Welded Bonded to glass Framed in field
\$5.28/W	\$0.80/W	\$0.05 to \$1.00/W

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Sequences

1975	1985	Future	
Acid etch	Texture	Acid etch	
Diffuse	Diffuse	Oxidize	
Etch	BSF	Mask front	
A-R coat	Clean	Etch	
Mask	Mask	Diffuse	
Etch	Edge etch	Mask front	
Plate	Print back	Etch back and edge	
Clamp mask	Print grid	Etch front	
Edge etch	Fire	Passivate front and back	
Solder dip	A-R coat	Align and mask front and back	
Clean flux	Test	Etch	
Test		Metallize front and back	
Hand solder interconnect	Ribbon solder	BSR	
Clean flux	Clean flux	Test	
Prime glass	Bond glass	Weld	
Pot	Frame	Bond glass	
Frame	Test	Frame	
Test		Test	
\$30.00/W*	\$5.00/W*	\$2.00 to \$10.00/W	

*With yield and profit.